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APPLICATION NO. FILING DATE		G DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/046,330	10/2:	5/2001	Wuwen Yi	JM32810-CIP (HO57-232)	1884
21567	7590	07:30/2003			
	Γ. JOHN P.S		EXAMINER		
601 W. FIRST AVENUE, SUITE 1300 SPOKANE, WA 99201				DANG, PHUC T	
				ART UNIT	PAPER NUMBER
				2818	

DATE MAILED: 07/30/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

	·	Application No.	Applicant(s)					
		10/046,330	YI ET AL.					
	Office Action Summary	Examiner	Art Unit					
		PHUC T DANG	2818					
	The MAILING DATE of this communication a		with the correspondence address					
Period for	• •							
THE - External after of the control	ORTENED STATUTORY PERIOD FOR REP MAILING DATE OF THIS COMMUNICATION ensions of time may be available under the provisions of 37 CFR 1 SIX (6) MONTHS from the mailing date of this communication. The period for reply specified above is less than thirty (30) days, a reduce to reply within the set or extended period for reply will, by stature to received by the Office later than three months after the mail ed patent term adjustment. See 37 CFR 1.704(b).		v a reply be timely filed thirty (30) days will be considered timely. IONTHS from the mailing date of this communication. ABANDONED (35 U.S.C. § 133).					
1)⊠	Responsive to communication(s) filed on 29	May 2003 .						
2a)□		This action is non-final.						
3)	Since this application is in condition for allow closed in accordance with the practice under							
·	ion of Claims							
4)⊠	Claim(s) <u>1-30</u> is/are pending in the application							
<b>5\</b> \	4a) Of the above claim(s) is/are withdrawn from consideration.							
5)⊠ c)⊠								
	Claim(s) <u>1-6</u> is/are rejected.							
•	Claim(s) is/are objected to.	lor election requirement						
, —-	Claim(s) are subject to restriction and ion Papers	or election requirement.						
	The specification is objected to by the Examir	ner.						
,	The drawing(s) filed on <u>25 October 2001</u> is/ar		bjected to by the Examiner.					
,	Applicant may not request that any objection to							
11)[	The proposed drawing correction filed on	is: a)□ approved b)□	disapproved by the Examiner.					
	If approved, corrected drawings are required in r	reply to this Office action.						
12)	The oath or declaration is objected to by the E	Examiner.						
Priority (	under 35 U.S.C. §§ 119 and 120							
13)	Acknowledgment is made of a claim for foreign	gn priority under 35 U.S.	C. § 119(a)-(d) or (f).					
a)	☐ All b)☐ Some * c)☐ None of:							
	1. Certified copies of the priority documents have been received.							
	2. Certified copies of the priority document	nts have been received in	Application No					
* (	3. Copies of the certified copies of the pri application from the International E See the attached detailed Office action for a lis	Bureau (PCT Rule 17.2(a	)).					
14) 🔲 /	Acknowledgment is made of a claim for domes	stic priority under 35 U.S.	C. § 119(e) (to a provisional application).					
	a)  The translation of the foreign language p Acknowledgment is made of a claim for dome							
Attachmer	nt(s)							
2) Noti	ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449) Paper No(s)	5) Notice	ew Summary (PTO-413) Paper No(s) of Informal Patent Application (PTO-152)					

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#### **DETAILED ACTION**

#### Oath/Declaration

1. The oath/declaration filed on October 28, 2001 is acceptable.

### **Specification**

2. The specification has been checked to the extent necessary to determine the presence of all possible minor errors. However, the applicant's cooperation is requested in correcting any errors of which applicant may become aware in the specification.

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(f) or (g) prior art under 35 U.S.C. 103(a).

3. Claims 1-6 are rejected under 35 U.S.C. 103(a) as being unpatentable over Lauth et al. (U.S. Patent No. 5,559,065).

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Regarding claims 1-6, Lauth et al. teach a non-magnetic physical vapor deposition consisting essentially of Co or Ni and silicon [col. 1, lines 1-col. 5, lines 24].

Lauth et al. disclose all the features of the claimed invention as discussed above, but do not disclose one phase is applied in the process of Co or Ni and silicon target.

One phase is applied in the process of Co or Ni and silicon target is considered to be obvious in variation design, since any sputtering target used to define the time as the wafer stays in the furnace at high temperature. Thus, it would have been obvious to one skilled in the art to use one phase of Co or Ni and silicon in the process for a purpose of preventing defects on the silicon wafer.

## Allowable Subject Matter

4. Claims 7-30 would be allowed.

The following is a statement of reason for the indication of allowable subject matter:

Claims 7-30 are considered allowable since the prior art of record and the considered pertinent to the applicant's disclosure does not teach or suggest the claimed invention. Hu et al. (U.S. Patent No. 5,763,923) do not teach the claimed invention having one phase comprising cobalt, and not more than 1% of any additional phases comprising cobalt other than one phase as recited in claim 7 and one phase comprising nickel, and not more than 1% of any additional phases comprising nickel other than one phase as recited in claim 16 and one phase comprising the one or more of Co, Ni, Ta, Ti, Pt, and Mo and not more than 1% of any additional phases comprising the one or more of Co, Ni, Ta, Ti, Pt and Mo other than the one phase; wherein the target is non-magnetic as recited in claim 22 and one phase comprising WSi<sub>2</sub> and not more than 1% of any

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additional phases other than one phase; and wherein the target is non-magnetic as recited in claim 29.

#### Conclusion

- Any inquiry concerning this communication or earlier communications from the 5. examiner should be directed to Phuc T. Dang whose telephone number is 703-305-1080. The examiner can normally be reached on 8:00 am-5:00 pm.
- If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David C. Nelms can be reached on 703-308-4910. The fax phone numbers for the organization where this application or proceeding is assigned are 703-308-7722 for regular communications and 703-308-5841 for After Final communications.
- Any inquiry of a general nature or relating to the status of this application or 7. proceeding should be directed to the receptionist whose telephone number is 703-308-PP Jangrinu 0956.

Phuc T. Dang

Examiner

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July 15, 2003